What is claimed is:

1. A diffraction pattern intensity analysis method used to analyze intensity of visible light emitted from a diffraction pattern of a fluorescent screen as a result of reflection high-energy electron diffraction, comprising the steps of:

using a photoreceptor to measure the intensity of the diffraction pattern that appears on the fluorescent screen, via a halation-prevention filter with a transmittance which is minimum at a filter center and increases with distance from the filter center;

based on a result of the measurement, obtaining a rate of decrease in the intensity of the visible light transmitted through the filter; and

correcting the diffraction pattern intensity measured by the photoreceptor, based on the decrease rate.

2. The diffraction pattern intensity analysis method of claim 1, in which the transmittance of visible light transmitted through the filter increases in proportion to r^n, where r is a distance from the filter center.

3. A diffraction pattern intensity correction program for use with an image analysis device having a fluorescent screen for creating a diffraction pattern that results from reflection high-energy electron diffraction, a photoreceptor for optically acquiring the diffraction pattern that appears on the fluorescent screen, and a halation-prevention filter for location along a light path connecting the fluorescent screen and the photoreceptor, in which a transmittance of the visible light transmitted through the filter is minimum at a center of the filter and increases with a distance from the center, the program comprising:

a measured intensity storage means for storing an intensity of visible light emitted from the diffraction pattern on the fluorescent screen as a result of reflection high-energy electron diffraction, passed through the halation-prevention filter and detected by the photoreceptor means;

an intensity decrease rate storage means for storing a rate of decrease in the intensity of the visible light transmitted through the halation-prevention filter; and

a corrected-intensity computation means for computing a corrected intensity of the diffraction pattern by correcting the intensity stored by the measured intensity storage means, based on the decrease rate stored by the intensity decrease rate storage means.

4. The diffraction pattern intensity correction program of claim 3, further comprising:

a point light source;

an emission controller for controlling the generation of light by the point light source;

an intensity measurement means for measuring, via the photoreceptor, the intensity of the visible light emitted from the diffraction pattern of the fluorescent screen and the intensity of the point light source-emitted visible light that passed through the filter;

an intensity decrease rate computation means for computing a rate of decrease in the intensity of the visible light transmitted through the filter, based on the intensity of the visible light emitted by the point light source, that was measured by the intensity measurement means; and

a corrected-intensity computation means that, based on the decrease rate computed by the intensity decrease rate computation means, computes the corrected intensity used to correct the intensity of the visible light emitted from the diffraction pattern of the fluorescent screen, that was measured by the photoreceptor.